

In re: Chung et al.  
Serial No.: 10/047,706  
Filed: Chung et al.  
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Applicants also request entry of the Supplemental Information Disclosure Statement and accompanying PTO Form-1449 submitted herewith.

In view of the above, Applicants respectfully request favorable examination and allowance of the present application.

Respectfully submitted,



Mitchell S. Bigel  
Attorney for Applicant  
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Customer Number:

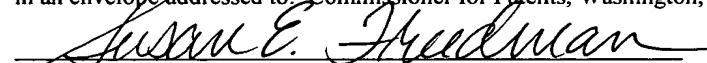


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**CERTIFICATE OF MAILING**

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to: Commissioner for Patents, Washington, DC 20231, on March 14, 2002.

  
Susan E. Freedman

Date of Signature: March 14, 2002

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VERSION WITH MARKINGS TO SHOW CHANGES MADE

In the Specification:

The paragraph beginning at page 13, line 11, has been replaced with the following paragraph:

According to Si-woo [Lee] Rhee et al., "Chemical Vapor Deposition Precursors for (Ba, Sr)TiO<sub>3</sub> Films", 6<sup>th</sup> Korean Semiconductor Seminar, the deposition of Ti may be carried out using the surface reaction as a rate determining step, and high coverage may be achieved by virtue of the surface movement of Ti.